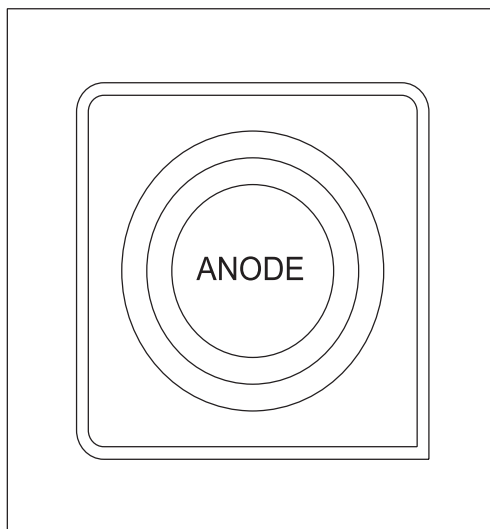


PROCESS DETAILS

| | |
|------------------------|-------------------|
| Process | EPITAXIAL PLANAR |
| Die Size | 9.0 x 9.0 MILS |
| Die Thickness | 7.1 MILS |
| Anode Bonding Pad Area | 4.8 MILS DIAMETER |
| Top Side Metalization | Al - 30,000Å |
| Back Side Metalization | Au - 12,000Å |

GEOMETRY



BACKSIDE CATHODE

R0

GROSS DIE PER 4 INCH WAFER

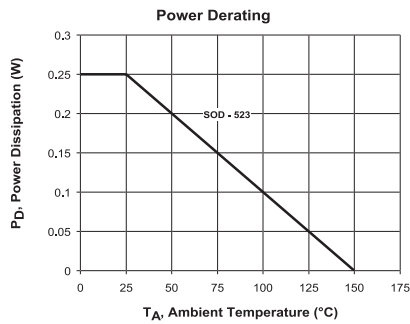
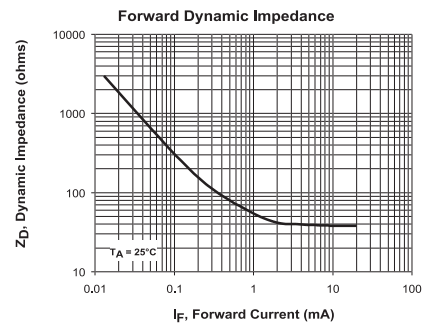
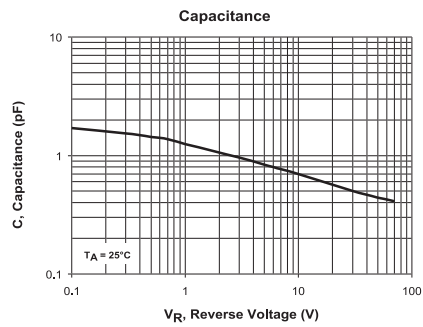
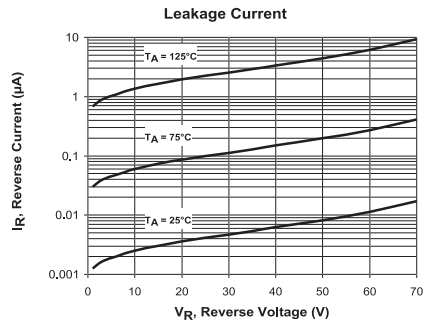
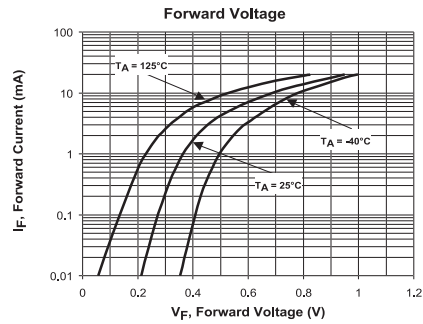
139,050

PRINCIPAL DEVICE TYPES

CMDD6263
CMKD6263
CMLD6263 Series
CMOD6263
CMPD6263 SERIES
CMSD6263 SERIES
CMUD6263 Series
1N6263

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